



## China Compound Semiconductor Standards Committee

### Meeting Agenda

China Fall Standards Meeting  
Wednesday, September 22<sup>nd</sup>, 2021, 13:30 --16:45  
Wuhu, Anhui, China

<b>Time</b>	<b>Topic</b>	<b>Presenter</b>
13:00	<b>Registration</b>	
13:30	<b>Welcome / Call to Order</b> <ul style="list-style-type: none"><li>• Opening Remark</li><li>• Introductions</li><li>• Meeting Reminders</li><li>• Agenda Review</li></ul>	Co-chair All SEMI Staff Co-chair
13:50	<b>Review and Approval of Previous Meeting Minutes</b>	SEMI Staff
13:55	<b>SEMI Staff Report</b>	SEMI Staff
14:00	<b>Liaison Reports</b> <ul style="list-style-type: none"><li>• North America CSM Committee</li><li>• Europe CSM Committee</li><li>• Japan CSM Committee</li></ul>	SEMI Staff SEMI Staff SEMI Staff
14:15	<b>TF Reports</b> <ul style="list-style-type: none"><li>• SiC Epitaxial Wafer Task Force</li><li>• Silicon Carbide Substrate Task Force</li></ul>	Gan FENG – Epiworld Min LU – MigeLab
15:00	<b>Documents Request for Ballots</b> <ul style="list-style-type: none"><li>• Doc. 6693, New Standard: Specification for 4H-SiC Homo-Epitaxial Wafer</li><li>• Doc. 6767, Test Method for Flatness of Silicon Carbide Wafers by Optical Interference</li><li>• Doc. 6768, Test Method for Micropipe Density of Silicon Carbide Wafer by Laser Reflection</li><li>• Doc. 6769, Test Method for Residual Stress of Silicon Carbide Wafers by Photoelastic</li></ul>	Gan FENG – Epiworld Min LU – MigeLab Min LU – MigeLab Min LU – MigeLab
16:00	<b>New Action Items</b>	SEMI Staff
16:05	<b>Next Meeting Date &amp; Locale</b> <ul style="list-style-type: none"><li>• Next Meeting Time of the China Compound Semiconductor Materials Standards Committee</li></ul>	
16:10	<b>Group Photo</b>	
16:20	<b>Core Members Application and Renew</b>	
16:45	<b>Adjournment</b>	